

ABSTRACT OF THE DISCLOSURE

Disclosed is a phase shift mask capable of assuring high-precision pattern transfer, an exposure method and apparatus using such phase shift mask, and a device manufacturing method using such phase shift mask. The phase shift mask includes a substrate having an engraved portion and a non-engraved portion, the engraved portion having a side wall and a bottom face, and a light blocking film provided in a portion of the bottom face and the side wall of the engraved portion. Specifically, the size to be defined by subtracting a thickness of the light blocking film at the side wall from a width of the engraved portion is made equal to 1.3 to 2.4 times the width of a light transmitting portion provided at the engraved portion.